

**OS3: The First International Symposium on Integrated Flow Science IV  
Advanced Semiconductor and Digital Transformation**

November 7, 2023  
EX-3-A

- OS3-1        **The Digital Transformation in Health Care and Education Setting (*Invited*)**  
13:10-13:40   Guang Hong, Nobuhiro Yoda, Hiroshi Egusa, Ken Osaka (Tohoku University, Japan)
- OS3-2        **Exploring the Boundary Layer Dynamics on Rotating Substrates for Enhanced Wet  
Cleaning Efficiency (*Invited*)**  
13:40-14:10   Naser Belmiloud (SCREEN SPE Germany GmbH, Germany), Mizuki Kihara,  
Masanobu Sato, Yasutoshi Okuno (SCREEN Semiconductor Solutions Co., Ltd,  
Japan)
- OS3-3        **Silicon Technologies for Quantum Computing (*Invited*)**  
14:10-14:40   Takahiro Mori (National Institute of Advanced Industrial Science and Technology  
(AIST), Japan)
- OS3-4        **Significant Device Performance Enhancement of 1L MoS<sub>2</sub> nMOSFETs through the  
vdW Interface Formation of Sb<sub>2</sub>Te<sub>3</sub>/MoS<sub>2</sub>**  
14:50-15:10   Wen Hsin Chang, Shogo Hatayama, Yuta Saito, Naoya Okada (National Institute of  
Advanced Industrial Science and Technology (AIST), Japan), Takahiko Endo,  
Yasumitsu Miyata (Tokyo Metropolitan University, Japan), Toshifumi Irisawa  
(National Institute of Advanced Industrial Science and Technology (AIST), Japan)
- OS3-5        **Formation of *In-situ* Al Doped SiC Thin Film.**  
15:10-15:30   Yuuki Tsuchiizu (Aichi Institute of Technology, Japan), Kouki Ono (Nagoya  
University, Japan), Kennichi Uehara, Sigeo Yasuhara (Japan Advanced Chemicals  
Ltd., Japan), Wakana Takeuchi (Aichi Institute of Technology, Japan)
- OS3-6        **Suppression of Charges in Al<sub>2</sub>O<sub>3</sub> Gate Dielectric and Improvement of MOSFET  
Performance by Plasma Nitridation**  
15:30-15:50   Kenzo Manabe (National Institute of Advanced Industrial Science and Technology  
(AIST), Japan)